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Engineering erbium-doped oxide thin layers for integrated photonics

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Objective and motivation

We envision the hybrid integration of erbium-doped crystalline functional oxides on silicon photonics platform to develop new integrated light sources and optical amplifiers [1].

Main challenges:

- Grow high crystalline quality films
- Engineer high doping concentration of erbium;
- Reducing propagation loss [2]

Hybrid integration on SiN_x photonic platform

Implemented Er:YSZ on SiO₂ buried SiN_x waveguides on Si.

- Optimum Er:YSZ/Er³⁺ thickness simulations
 (λ=1550 nm):
 - ✓ Trade off in mode confinement in Er and SiN_x waveguide.



• Avoid quenching effects

Er:YSZ

10⁴ T

Synthesis and Structure

- Growth of Erbium-doped yttria stabilized-zirconia (Er:YSZ) thin films:
 - ✓ Epitaxially on sapphire by Pulsed Laser
 Deposition (PLD) at 800°C in O₂ atmosphere.
 ✓ different concentrations of erbium .
- **X-ray diffraction**: two YSZ orientations (111) and (001).
- Energy-filtered transmission electron microscopy (EFTEM) for non doped YSZ proves same preferred orientations [3].

06)

YSZ



Erbium

✓ Reduction of propagation loss

Simulation results for Er:YSZ thicknesses of 150 and 350 nm:

Mode's fraction confined in YSZ (electric field intensity):



• Visible spectroscopy (pump wavelength at 1480 nm) \checkmark up-conversion luminescence of Er ions at 525, 544, 562, 656 and 679 nm from ${}^{2}H_{11/2} \rightarrow {}^{4}I_{15/2}$, ${}^{4}S_{3/2} \rightarrow {}^{4}I_{15/2}$, ${}^{2}H_{9/2} \rightarrow {}^{4}I_{13/2}$, ${}^{4}F_{9/2} \rightarrow {}^{4}I_{15/2}$ and ${}^{2}H_{9/2} \rightarrow {}^{4}I_{11/2}$ transitions, respectively [5].

 \checkmark At the shadow of these results, **optical gain might be expected** .



(200) (111)



Conclusions and perspectives

•PL studies with pumping at 980 nm on polycrystalline Er:YSZ on sapphire reveal that erbium doping of 3% provides highest efficiencies for 1.53 μ m emission.

•Local Stark effect has been observed with strong enhancement luminescence.

•Er:YSZ has been grown on integrated optical SiN_x devices .



4000 0 1510 1520 1530 1540 Wavelength(nm)

- Luminescence at 1530 nm (⁴I_{13/2}→ ⁴I_{15/2} transitions)
- Local Stark effect on same transition with enhanced intensity related to erbium emplacement within the oxide structure [4].

Strong erbium up-conversion is observed in Er:YSZ layers.

•Future work will focus on the study of gain in Er:YSZ on the hybrid SiN_x platform at 1.53 μ m to demonstrate on-chip optical amplifiers at telecom wavelengths.

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